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INFORMATION	Atty. Docket N .: 150.01180102	Serial No.: 10/771,050
DISCLOSURE STATEMENT	Applicant(s): Brian A. Vaartstra	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed:	April 26, 2004

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Cs		WO 98/36045	08/20/98	PCT				
CL		WO 99/27581	06/03/99	PCT				
CL		WO 99/53532	10/21/99	PCT				
Ca		WO 00/31794	06/02/00	PCT				

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CL		Ginzburg et al., Analytical Chemistry of Platinum Metals, John Wiley & Sons, New York, cover pg., and 14-15.
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